

introducing section having an opening thereof in an internal surface of said guide tube, for introducing said charged particles from said charged particle generator into said guide tube; and

a shield section located between said opening of said introducing section and said outlet aperture, the base of which being on the internal wall surface of said guide tube and being located at a position having a space from said opening of said introducing section, wherein said shield section comprises a shield surface making an acute angle with the internal wall surface of said guide tube.

2. The ion implantation apparatus according to Claim 1, wherein said shield section comprises a shield surface intersecting with straight lines running from points on a surface specified by said opening of said introducing section to points on a surface of said substrate to be implanted with the ions, placed in said ion implantation section.

3. The ion implantation apparatus according to Claim 1, wherein said shield section comprises a shield surface extending from the vicinity of the edge of said opening to above said opening.

4. (Amended) The ion implantation apparatus according to Claim 1, wherein said shield section comprises a shield surface intersecting with straight lines running from points on a surface specified by said opening of said introducing section to points on a surface specified by said outlet aperture of said beam guide section.

5. (Amended) The ion implantation apparatus according to Claim 2, wherein said shield surface has a flat plate shape.

6. (Amended) The ion implantation apparatus according to Claim 2, wherein said shield section comprises a flat plate having said shield surface, and a frame member for supporting said flat plate.